

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L4	16580	((local\$2 or selective\$2) same etch\$3) same (silicon near oxide or "SiO.sub.2")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/21 08:48
L5	8	L4 same (spray\$3 same gas\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/21 08:48
L6	1	yanagisawa-michihiko.in. and (local\$2 same etch\$3) same (silicon near oxide or "SiO.sub.2")	US-PGPUB; USPAT	OR	OFF	2006/04/21 08:54
L7	32	yanagisawa-michihiko.in.	US-PGPUB; USPAT	OR	OFF	2006/04/21 09:01
L8	14182	((dry or plasma) near etch\$3 and silicon and silicon near oxide and nozzle or eject\$3 and control\$4). clm.	US-PGPUB; USPAT	OR	OFF	2006/04/21 09:03
L9	14	((dry or plasma) near etch\$3) and silicon and (silicon near oxide) and (nozzle or eject\$3) and control\$4). clm.	US-PGPUB; USPAT	OR	OFF	2006/04/21 09:04

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L1	40	(etch\$3 same (silicon near oxide or "SiO.sub.2")) same (eject\$3 or nozzle)	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/21 13:18
L2	670	(etch\$3 same silicon) same (eject\$3 or jet\$4 or nozzle)	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/21 13:19
L3	107	(etch\$3 same silicon) same ((eject\$3 or jet\$4 or nozzle) same gas\$3)	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/21 13:29
L4	9	3 and (remov\$3 same oxide)	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/21 13:29
L5	15	3 and ((remov\$3 or etch\$3 or pattern\$3) same oxide)	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/21 13:28
L6	15	3 and ((remov\$3 or etch\$3 or pattern\$3) same oxide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/21 13:28
L7	552	(etch\$3 same silicon) same ((eject\$3 or jet\$4 or nozzle) same gas\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/21 13:29
L8	9	7 and (remov\$3 same oxide)	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/04/21 13:29